



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: STEGER

Examiner: UNKNOWN PRUCHNICK

Application No. 10/720,839

Group No. ~~2858~~ 2859

Filed: 11/24/2003

Confirmation No. 3615

Title: METHODS AND APPARATUS FOR
IN SITU SUBSTRATE TEMPERATURE
MONITORINGINFORMATION DISCLOSURE STATEMENT

US PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	Reference to Related Cases
SOX	1	6514376 B1	2003-02-04	Collins et al.	CL/5NS
	2	6605955 B1	2003-08-12	Costello et al.	-/-
	3	6635117 B1	2003-10-21	Kinnard et al.	-/-
	4	4919542	1990-04-24	Nulman et al.	ALREADY CITED BY EXAMINER
	5	5200023	1993-04-06	Gifford et al.	-/-
	6	5229303	1993-07-20	Donnelly, Jr. et al.	-/-
	7	5388909	1995-02-14	Johnson et al.	-/-
	8	5467732	1995-11-21	Donnelly, Jr. Et al.	-/-
	9	5490728	1996-02-13	Schietinger et al.	-/-
	10	5568978	1996-10-29	Johnson et al.	-/-
	11	5660472	1997-08-26	Peuse et al.	-/-
	12	5683180	1997-11-04	De Lyon et al.	-/-
	13	5746513	1998-05-05	Renken	-/-
	14	5755511	1998-05-26	Peuse et al.	-/-
	15	5769540	1998-06-23	Schietinger et al.	-/-
	16	5775808	1998-07-07	Pan	-/-
	17	5848842	1998-12-15	Peuse et al.	-/-
	18	5967661	1999-10-19	Renken et al.	-/-
	19	5996415	1999-12-07	Stanke et al.	-/-
	20	6062729	2000-05-16	Ni et al.	ALREADY CITED
	21	6082892	2000-07-04	Adel et al.	-/-
	22	6112595	2000-09-05	Stanke et al.	-/-
	23	6174080	2001-01-16	Jennings	-/-
	24	6179466	2001-01-30	Peuse et al.	-/-
SOX	25	6182510	2001-02-06	Stanke et al.	-/-
	26	6481886	2002-11-19	Narendmath et al.	-/-

OTHER DOCUMENTS

Examiner Initials	Cite No.	Description	T
SOX	27	Hirscher, Hans, "Electrostatic Chuck to Boost Your Yield", http://semiconductors.unaxis.com/en/chiponline_72dpi/issue5/c5p39_72.pdf (NO DATE)	
SOX	28	"Diffuse-Reflectance Infrared Fourier Transform (DRIFT) Spectroscopy", http://147.46.41.146/C~jii/DRIFT.htm (NO DATE)	
SOX	29	"DRS-1000™ vs. Other Techniques", http://www.thermionics.com/drs/drsvsptry.htm (NO DATE)	

EXAMINER: Stanley J. Pruchnick, Jr. Considered 5/16/05

10/720,839

508	30	"Chapter 6: Thermal Mass", http://www.seav.vic.gov.au/ftp/buildings/5starhousing/ESHousingManualCh06.pdf	(NO DATE)
	31	Ellingboe, Bert, " Plasma Processing in the Microelectronics Industry", http://www.physics.dcu.ie/~jpm/seminars/seminars00_01/intro_to_plasma_processing.PDF	(NO DATE)
	32	"In-Situ 4000 White Paper – Solving the problems of pyrometry and thickness measurement during MBE and MOCVD", http://www.svta.com/products/monitoring/IS4K_White%20Paper.pdf	(NO DATE)
	33	Thevenard, Laura, "Wafer Temperature Measurement by Infrared Spectroscopy", Ecole Polytechnique Promotion X2000, Rapport De Stage D'Option Scientifique	(NO DATE)
	34	Riebau, Rhianna A., « Photoluminescence Spectroscopy of Strained InGaAs/GaAs Structures », Thesis Paper, 2001	(NO MONTH)
✓	35	"Module 4: System Overview", Etch Systems – Unity II: Field Engineer Level I	(NO DATE)
508	36	U.S. Patent Application No.: 10/608,091 File Date: June 30, 2003 Attorney Docket Number: 015290-682 Inventor: Steger	

Examiner Signature	Stanley P. Pruchnicki	Date Considered	2005/MAY 16
-----------------------	-----------------------	--------------------	-------------